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MEMC 98-1451/2554.1  
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of Robert J. Falster et al.

Art Unit 1775

Serial No. 10/073,506

Filed February 11, 2002

Confirmation No. 6190

For THERMAL ANNEALING PROCESS FOR PRODUCING LOW DEFECT  
DENSITY SINGLE CRYSTAL SILICON

Examiner Matthew A. Anderson

November 19, 2003

AMENDMENT C

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TO THE COMMISSIONER FOR PATENTS,

SIR:

This amendment is in response to the Office action mailed August 19, 2003.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2.

**Remarks** begin on page 12.